Final Exam Example Problem (20 points) An ideal Schottky barrier is formed between a metal having work function $\Phi=4.8~eV$ and n-type Si (electron affinity $\chi=4.0~eV$, $E_g=1.11~eV$). The donor doping in the Si is $N_d=10^{18}~cm^{-3}$.

Calculate the barrier height Φ_B . Calculate the semiconductor work function Φ_S . Calculate the contact potential, i.e., built-in potential qV_0 .

Draw the energy band diagram for the metal-semiconductor interface showing Φ_B , Φ_S , and qV_0 .